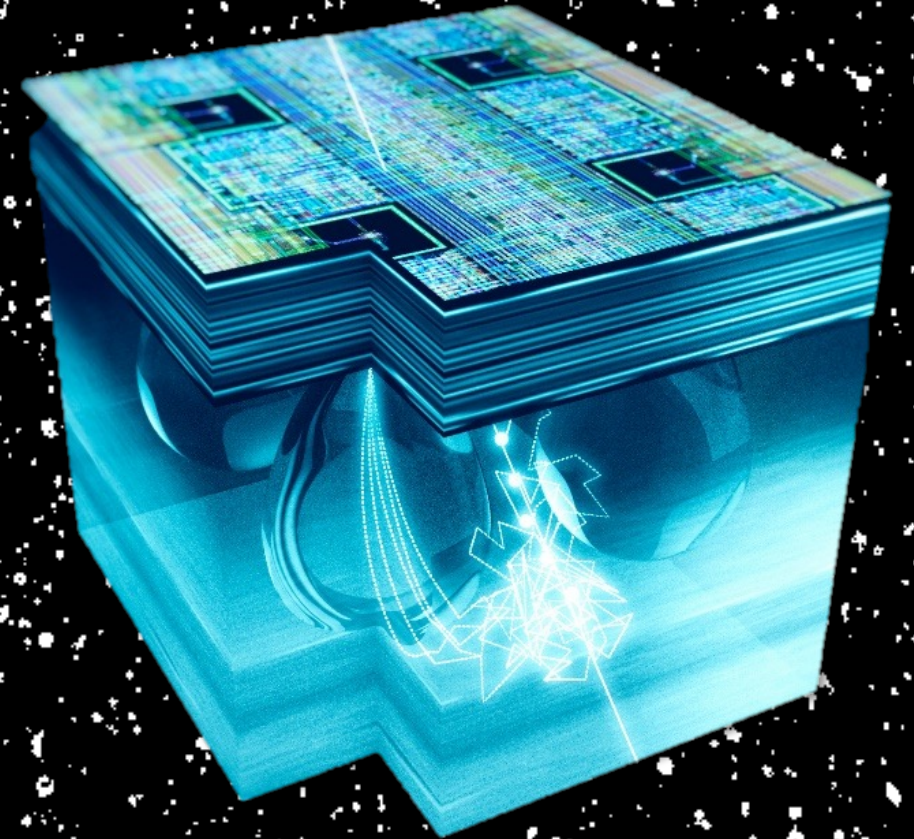


CMOS Monolithic Active Pixel Sensors



ALPIDE prototype: 200 MeV protons at PSI

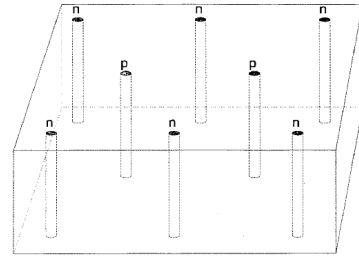
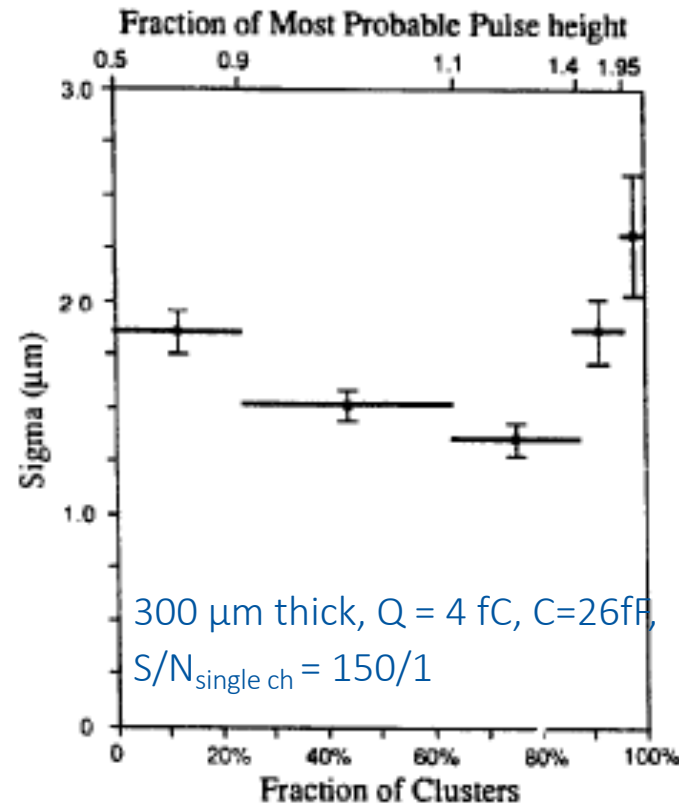
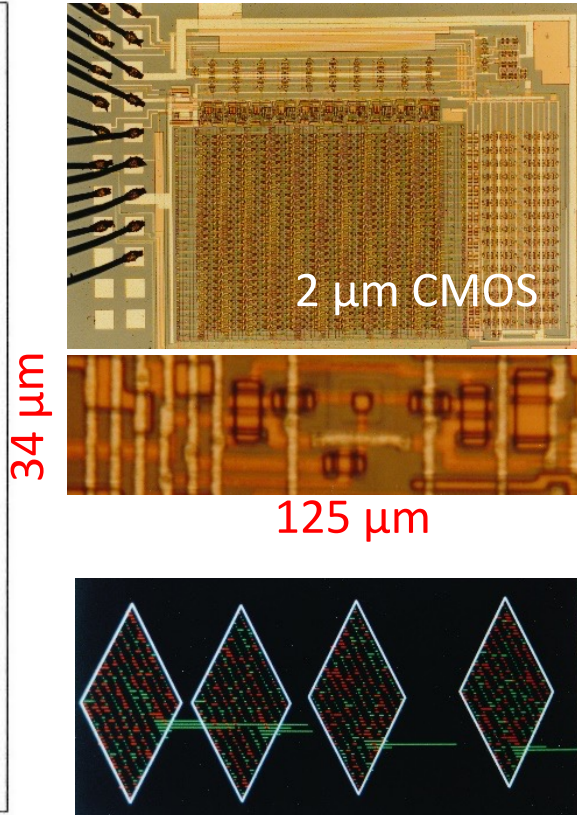
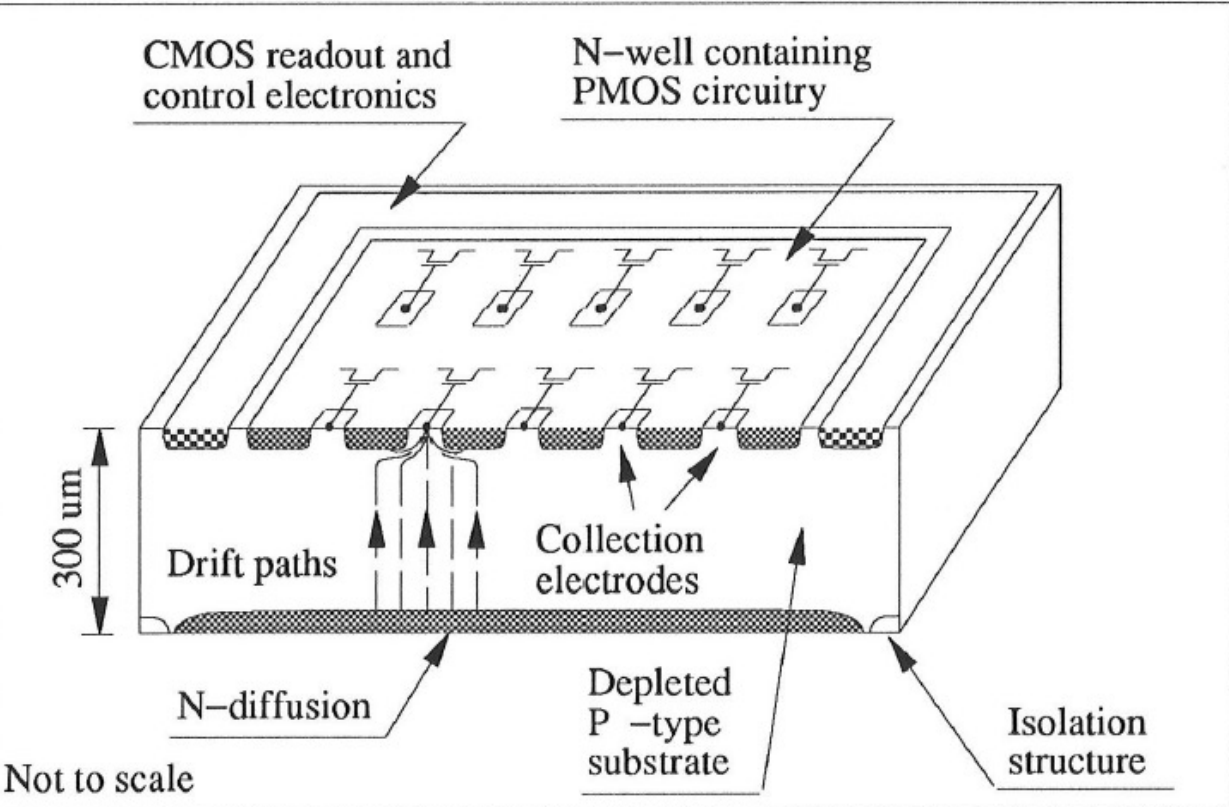
Walter Snoeys

Acknowledgements

- ICFA and the selection committee
- Marc Winter and Renato Turchetta for their key contribution, friendly contacts over these many years, and nice continued collaboration with IPHC and STFC.
- KULeuven, integrated accelerometer: L. Reynaert, B. Puers, W. Sansen (1943 – 2024)
- Stanford U.: S. Parker, C. Kenney, J. Segal, J. Plummer, G. Rosseel, C. H. Aw ... and BAEF fellowship
- Colleagues from CERN & the ESE group, the ALICE ITS2 &3 upgrade, ATLAS ITk, CLIC, EP R&D WP1.2 ... and **the foundries !**
 - Hybrid pixels: M. Campbell and E. Heijne, E. Cantatore, R. Dinapoli, L. Scharfetter ... and WA97, NA57, ALICE, LHCb
 - TOTEM and VFAT: K. Eggert, E. Radermacher, A. Scribano, V. Avati, M. Deile, P. Aspell, G. Antchev, E. Oliveri, N. Turini ...
 - C4i – Mind & collaboration with the Haute Savoie Dept: H. Mugnier, J. Rousset, S. Pothier, JM Thenard, D. Lajust, ...
- Monolithic: T. Kugathasan, G. Aglieri, M. Munker
 - LePIX (IBM 90nm): A. Marchioro, P. Giubilato, S. Mattiazzo, D. Pantano, A. Potenza, A. Rivetti ...
 - ALICE ITS2 & 3 : L. Musa, M. Mager, F. Reidt, W. Riegler, A. Kluge, C. Hu, C. Colledani, ...
 - ATLAS Itk & Stream: H. Pernegger, P. Riedler, P. Pangaud, M. Barbero, P. Schwemling, N. Wermes, G. Iacobucci, V. Dao, ...
 - CLIC and FASTPIX: D. Dannheim, K. Dort, J. Braach, E. Buschmann, ...
 - EP R&D WP1.2: P. Leitao, G. Ripamonti, G. Borghello, C. Lemoine, S. Emiliani, S. Bugiel, L. Ceccone, F. Piro ...
 - EP and ESE Management
- My family, my parents and my wife

and many, many others !!

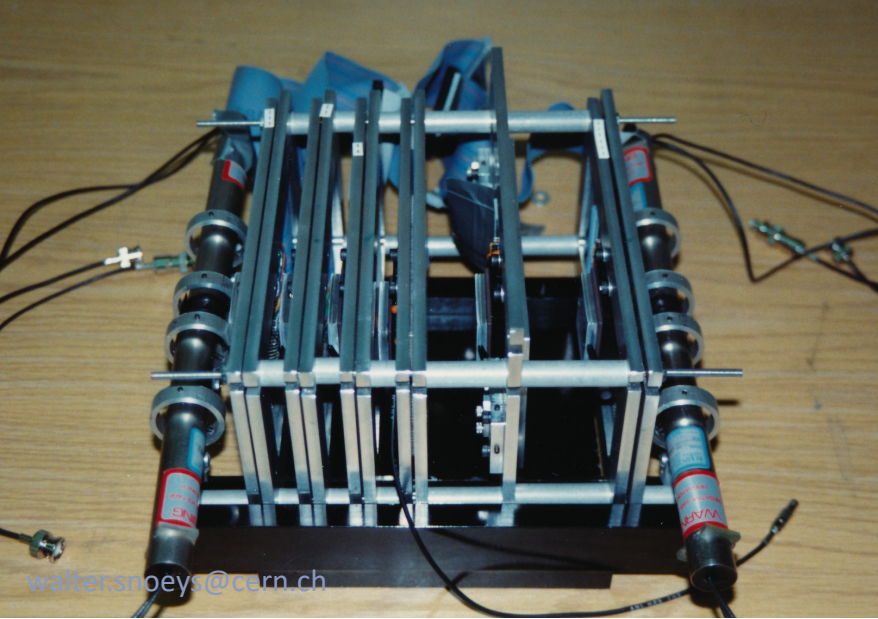
A monolithic detector for high energy physics (PhD thesis 1992), **CMOS with double sided processing**
 Stanford University 1987-1992, and the University of Hawaii
 First year funded by a fellowship from the **Belgian American Educational Foundation**.



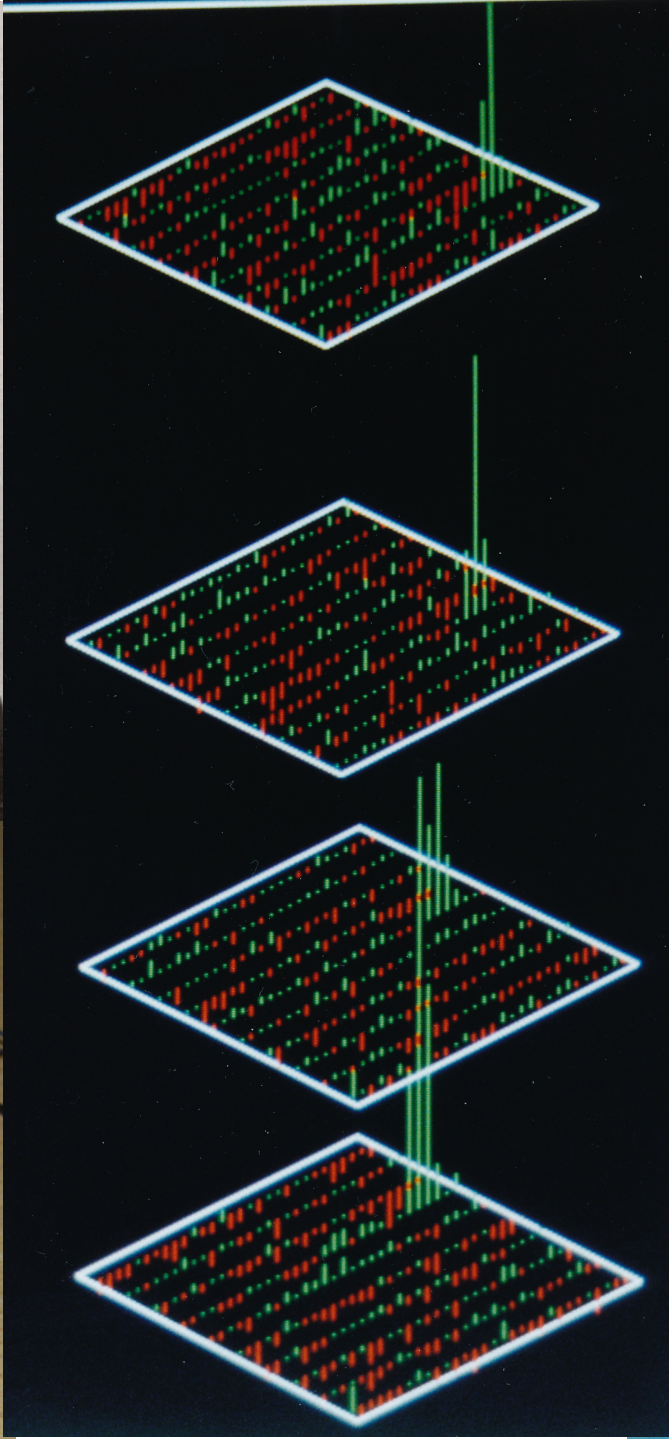
- Separation of junction from small collection electrode
- Better than 2 μm position resolution even at 34 μm pitch due to good S/N
- Improved back side trench isolation led to sensors with 3D electrodes (S.Parker, J. Segal)

C. Kenney, S. Parker, J. Plummer, J. Segal, W. Snoeys et al. NIM A (1994) 258-265, IEEE TNS 41 (6) (1994), IEEE TNS 46 (4) (1999)

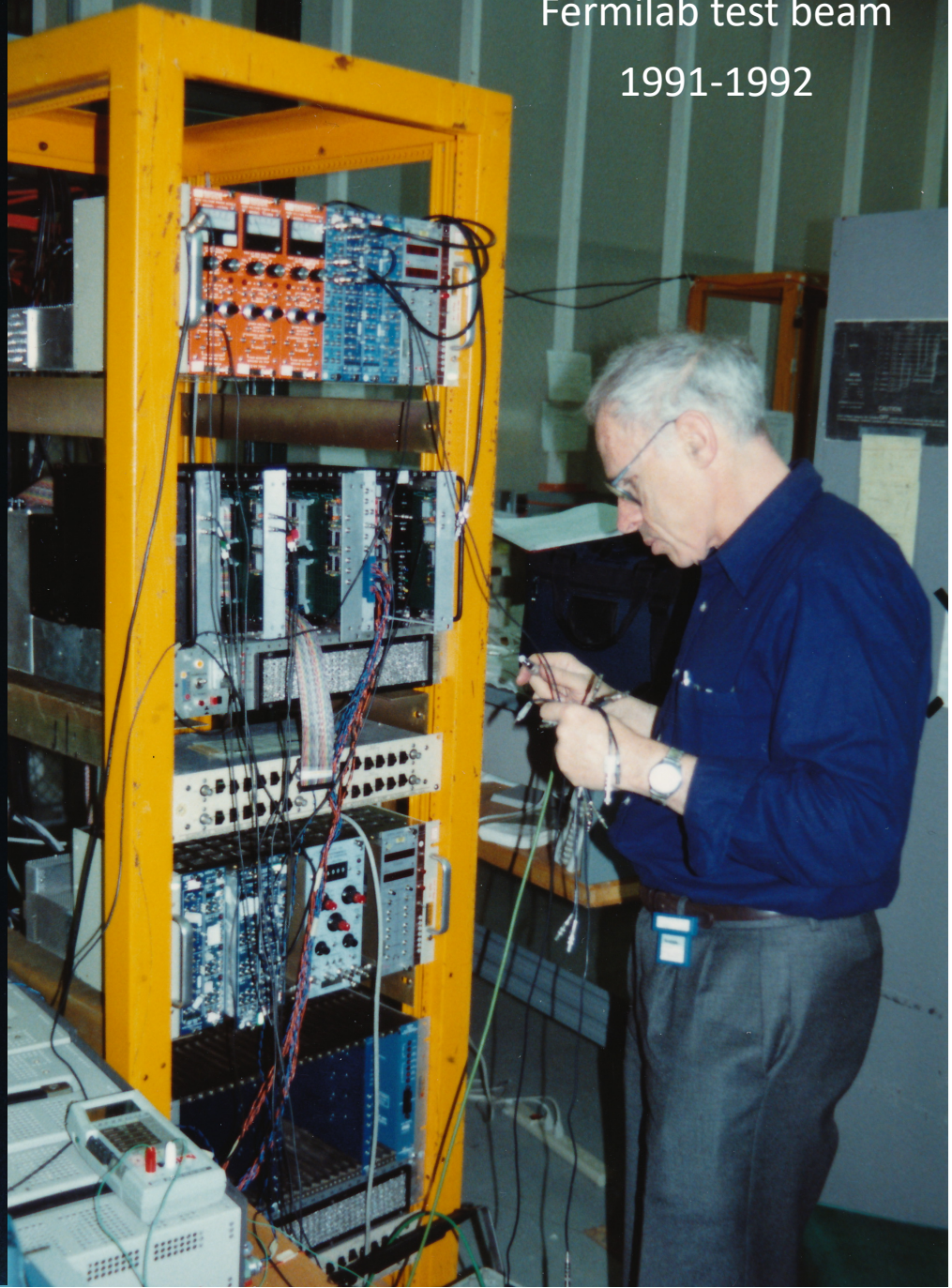
Sherwood Parker 1932 - 2018



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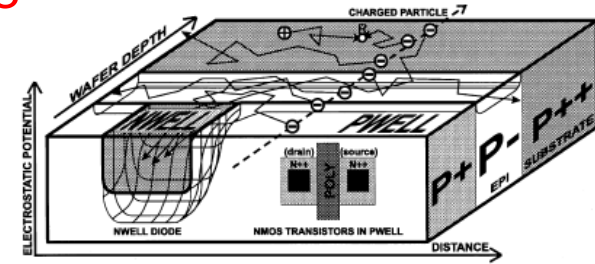
Fermilab test beam
1991-1992



KEY ENABLERS: *Mimosa series – IPHC Strasbourg - Move to standard CMOS*

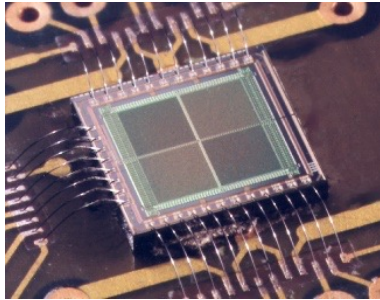
A monolithic active pixel sensor for charged particle tracking and imaging using standard VLSI CMOS technology

R. Turchetta^{a,*}, J.D. Berst^a, B. Casadei^a, G. Claus^a, C. Colledani^a, W. Dulinski^a, Y. Hu^a, D. Husson^a, J.P. Le Normand^a, J.L. Riestler^a, G. Deptuch^{b,1}, U. Goerlach^b, S. Higuere^t, M. Winter^b



NIM A 458 (2001) 677-689

Mimosa1 – 1999
AMS 0.6 μm



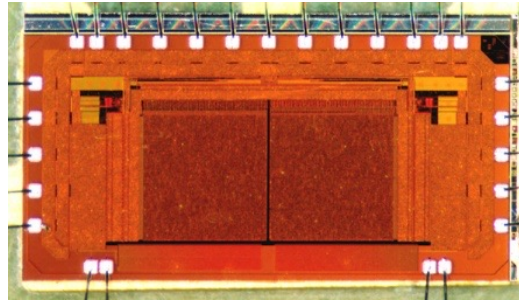
20μm pixel

Mimosa2 – 2000
MIETEC 0.35 μm



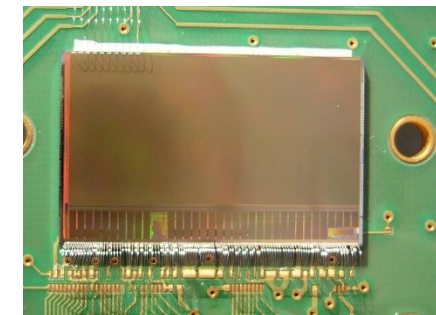
20μm pixel

Mimosa3 – 2001
IBM 0.25 μm



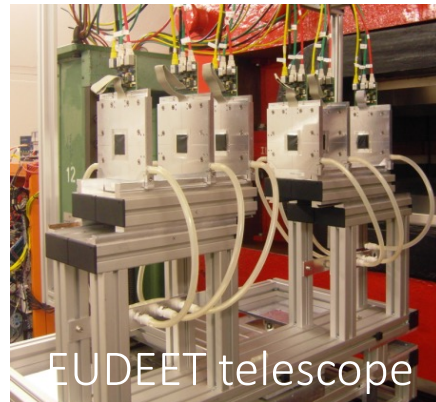
8μm pixel

Mimosa26 – 2008
AMS 0.35 μm



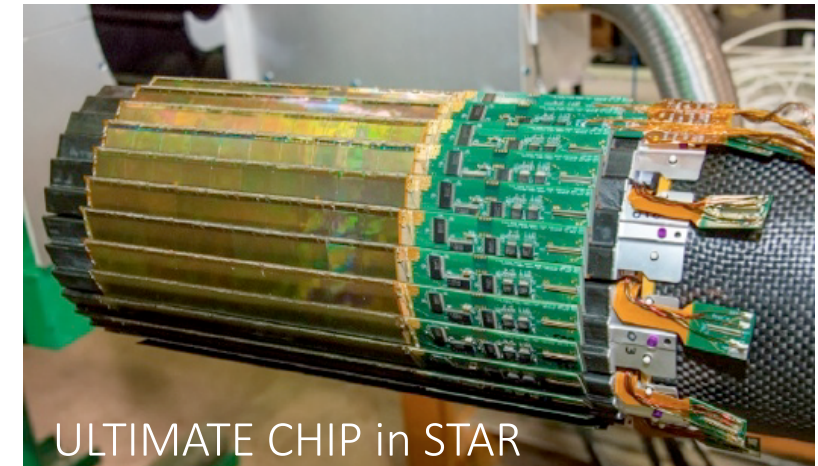
18.4 μm pixel

Mimosa26 – 2008 in the EUDET Telescope,



EUDET telescope

First use of MAPS in HEP



ULTIMATE CHIP in STAR

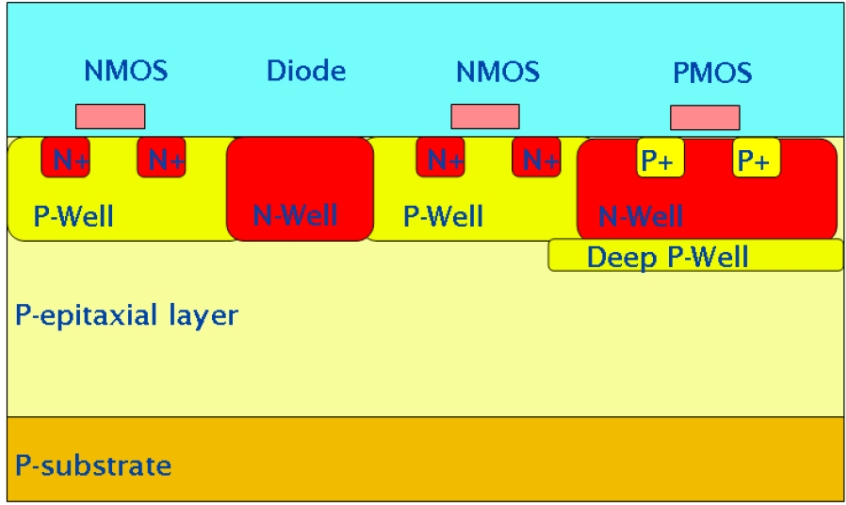
KEY ENABLERS: The INMAPS process: STFC development, in collaboration with TowerJazz: *a game changer*

Additional deep p-well implant allows *full CMOS in the pixel* and 100 % fill factor

Monolithic Active Pixel Sensors (MAPS) in a Quadruple Well Technology for Nearly 100% Fill Factor and Full CMOS Pixels

Jamie Alexander Ballin², Jamie Phillip Crooks¹, Paul Dominic Dauncey², Anne-Marie Magnan², Yoshinari Mikami^{3,**}, Owen Daniel Miller^{1,3}, Matthew Noy², Vladimir Rajovic^{3,***}, Marcel Stanitzki¹, Konstantin Stefanov¹, Renato Turchetta^{1,*}, Mike Tyndel¹, Enrico Giulio Villani¹, Nigel Keith Watson³, John Allan Wilson³

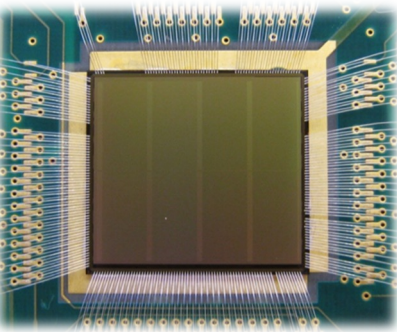
¹ Rutherford Appleton Laboratory, Science and Technology Facilities Council (STFC), Harwell Science and Innovation Campus, Didcot, OX11 0QX, U.K.
² Department of Physics, Blackett Laboratory, Imperial College London, London, SW7 2AZ, U.K.
³ School of Physics and Astronomy, University of Birmingham, Birmingham, B15 2TT, U.K.



Sensors 2008 (8) 5336, DOI:10.3390/s8095336

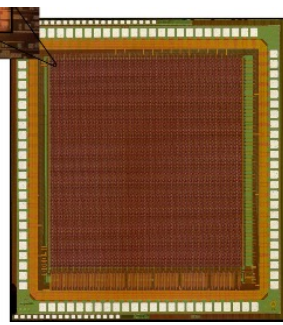
New generation of CMOS sensors for scientific applications in TowerJazz CIS 180nm

TPAC
ILC ECAL (CALICE)



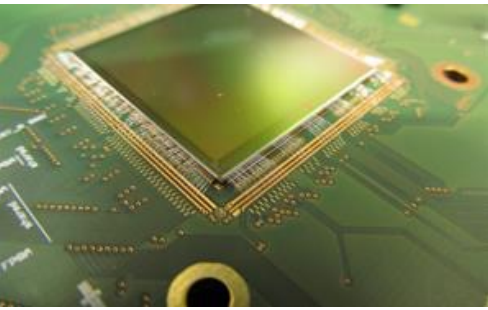
50µm pixel

DECAL
Calorimetry



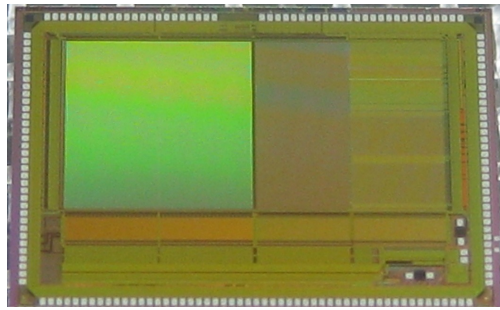
50µm pixel

PIMMS
TOF mass spectroscopy

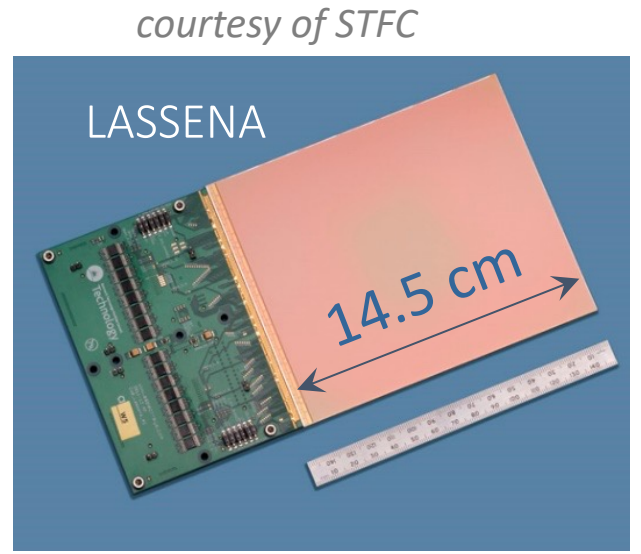


70µm pixel

CHERWELL
Calorimetry/Tracking



48 µm x 96 µm pixel

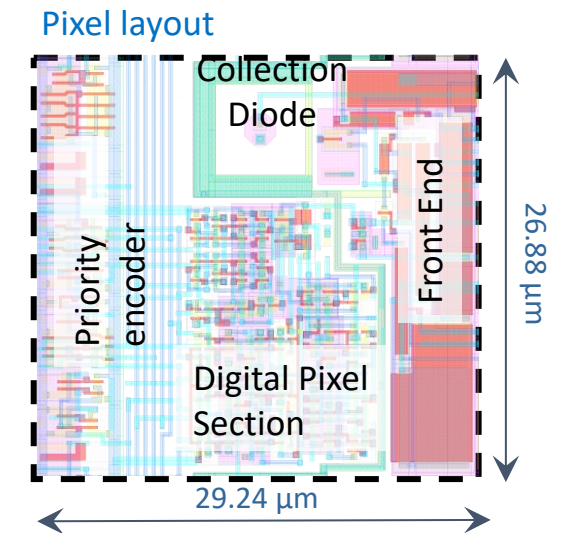
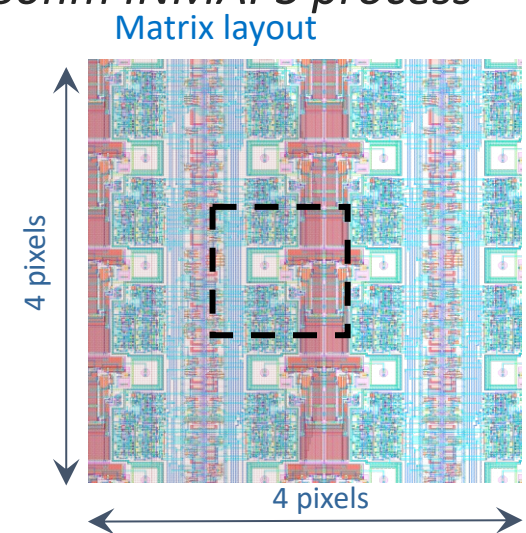
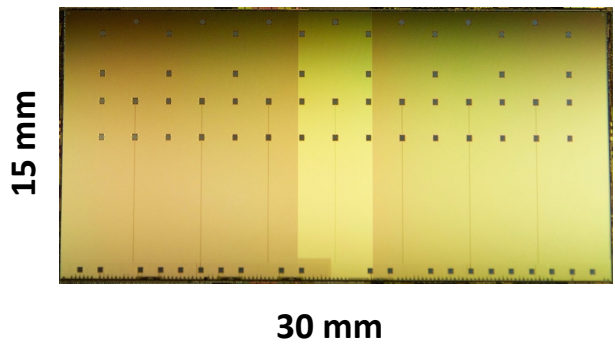
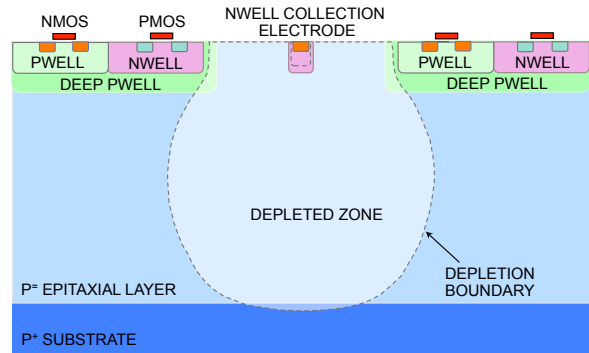


50µm pixel, *waferscale*

Standard INMAPS process also used for the ALPIDE (27 µm x 29 µm pixel) and MIMOSIS (CBM)

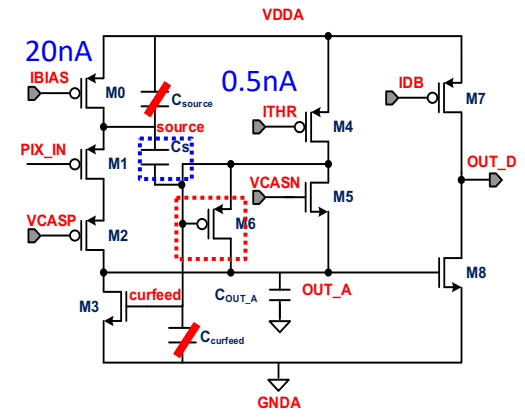
L. Musa et al.: The ALICE ITS2 and the ALPIDE chip in the T1 180nm INMAPS process

Also used for other applications



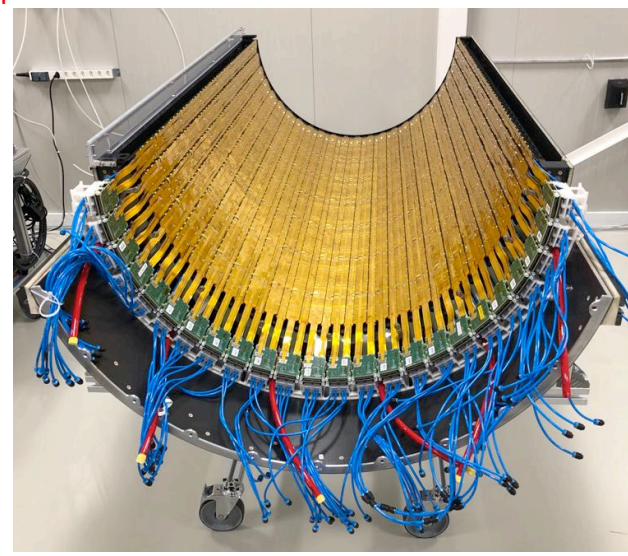
Zero-suppressed readout, no hits no digital power

G. Aglieri et al. NIM A 845 (2017) 583-587

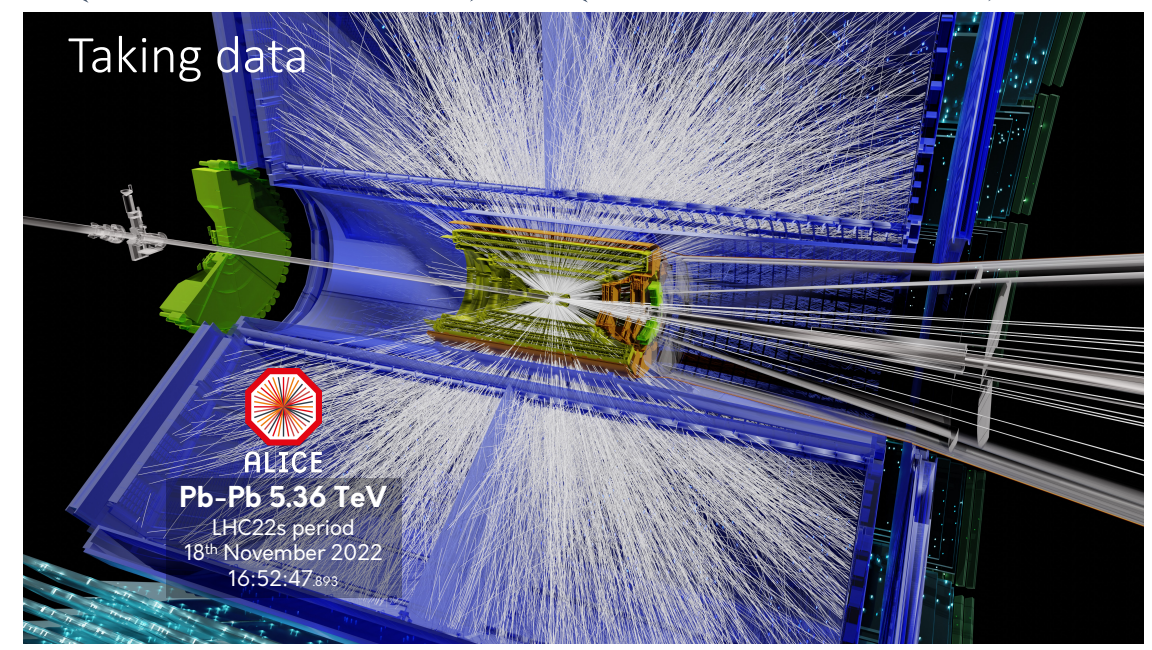


40 nW continuously active front end

D. Kim et al.
DOI 10.1088/1748-0221/11/02/C02042

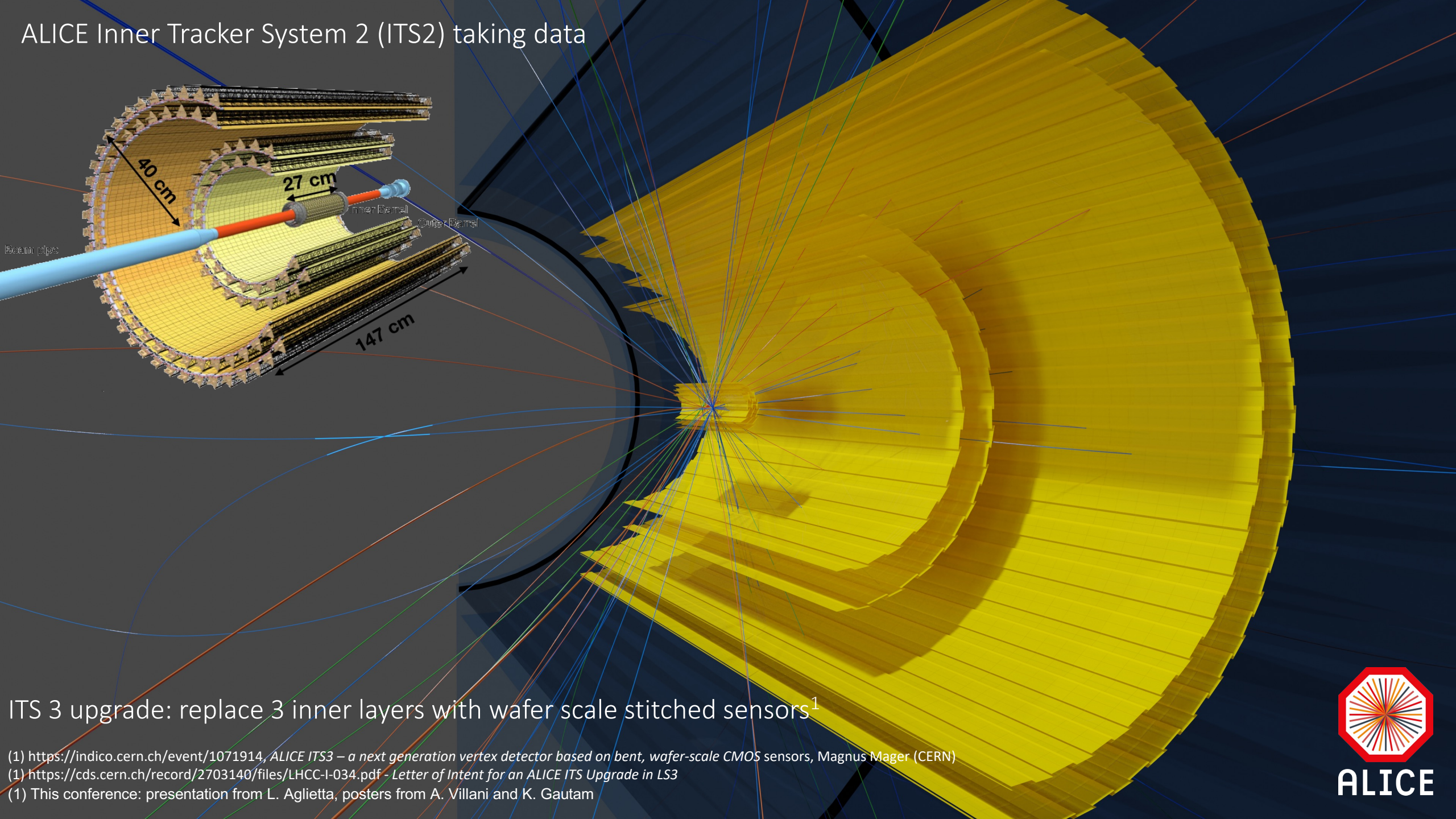


Half outer barrel (layer 6)
~ 2.47 Gpixels covering ~ 2 m² sensitive area



Design team: G. Aglieri, C. Cavicchioli, Y. Degerli, C. Flouzat, D. Gajanana, C. Gao, F. Guilloux, S. Hristozkov, D. Kim, T. Kugathasan, A. Lattuca, S. Lee, M. Lupi, D. Marras, C.A. Marin Tobon, G. Mazza, H. Mugnier, J. Rousset, G. Usai, A. Dorokhov, H. Pham, P. Yang, W. Snoeys (Institutes: CERN, INFN, CCNU, YONSEI, NIKHEF, IRFU, IPHC) and **comparable team for test**
1 MPW run and 5 engineering runs 2012-2016, production 2017-2018

ALICE Inner Tracker System 2 (ITS2) taking data



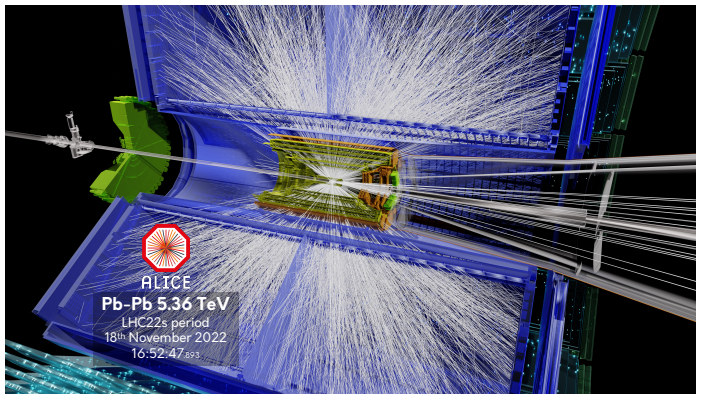
ITS 3 upgrade: replace 3 inner layers with wafer scale stitched sensors¹

(1) <https://indico.cern.ch/event/1071914>, ALICE ITS3 – a next generation vertex detector based on bent, wafer-scale CMOS sensors, Magnus Mager (CERN)
(1) <https://cds.cern.ch/record/2703140/files/LHCC-I-034.pdf> - Letter of Intent for an ALICE ITS Upgrade in LS3
(1) This conference: presentation from L. Aglietta, posters from A. Villani and K. Gautam

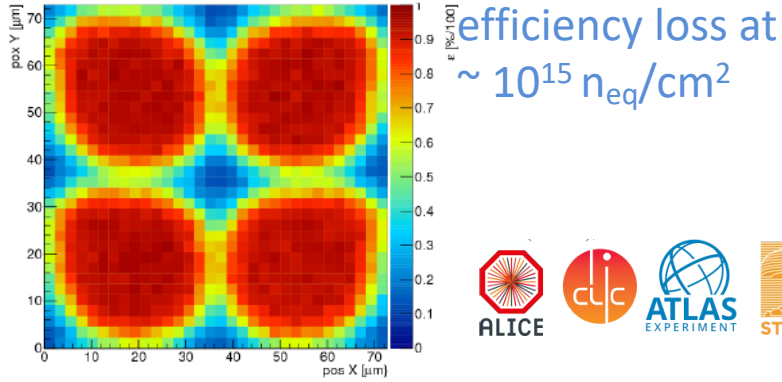


Pixel optimization for better margin: move junction away from the collection electrode for full depletion:
 Better time resolution, radiation hardness and ... efficiency, especially for thin sensors

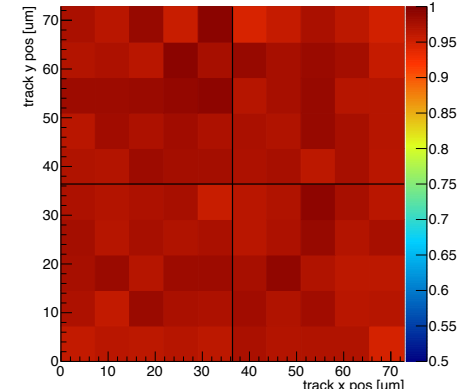
in 180 nm



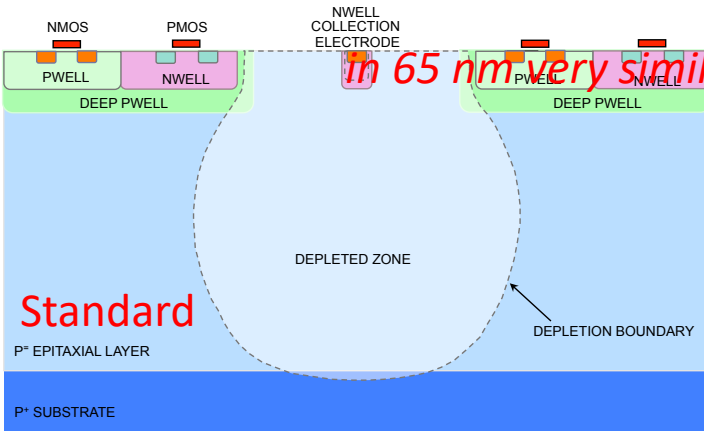
ALPIDE and ITS2 in ALICE (10 m²)



E. Schioppa et al, VCI 2019

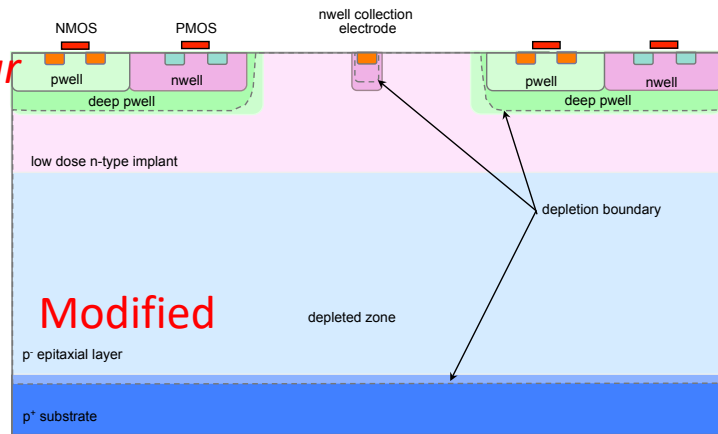


H. Pernegger et al., Hiroshima 2019,
 M. Dynda et al 2020 JINST 15 P0200



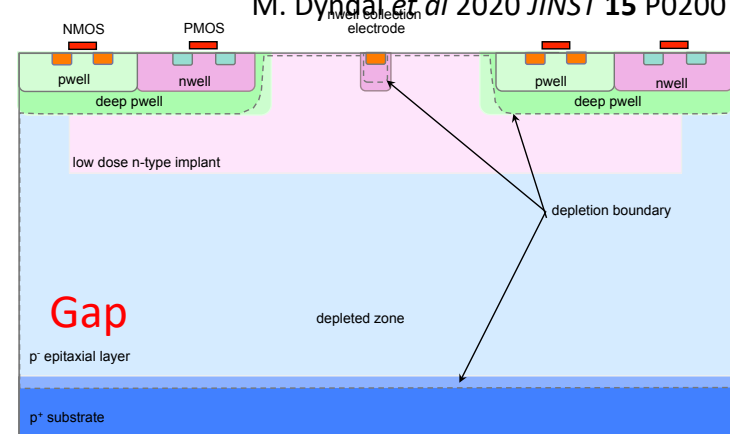
Standard

in 65 nm very similar



Modified

M. Munker et al.
<https://doi.org/10.1016/j.nima.2017.07.046> (180nm)



Gap

<https://iopscience.iop.org/article/10.1088/1748-0221/14/05/C05013>
 (180nm)

← Charge sharing

Charge collection speed →

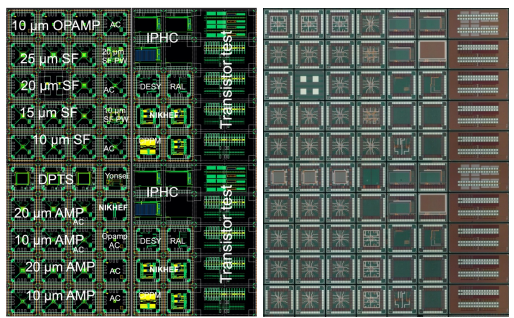
DOI: <https://doi.org/10.22323/1.420.0001> (65nm)

65 nm very similar, profited significantly from 10 years experience in 180 nm

EP R&D WP1.2 with a very significant contribution from ALICE ITS3 team (large measurement team 40-50 people)

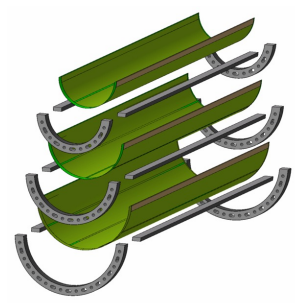
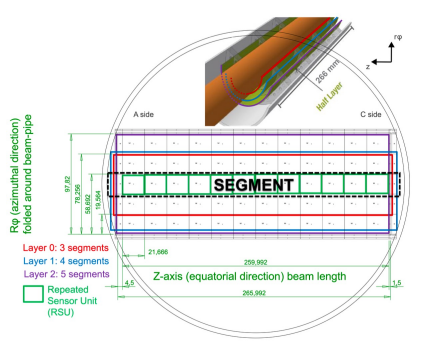
One slide on runs in 65 nm (MLR1, ER1 and ER2)

MLR1: Dec 2020: 1.5 x 1.5 mm² test chips qualification of TPSCo 65 nm for HEP



- Fully efficient at RT before and after $10^{15} n_{eq}/cm^2$
- Sensor time resolution ~ 70 ps (10 μm pitch)
- Investigating path to tolerance to higher irradiation levels and lower input capacitance (C. Lemoine *et al* 2024 JINST 19 C02033)

ER2: MOSAIX: Fall 2024: First full prototype for ALICE ITS3



walter.snoeys@cern.ch

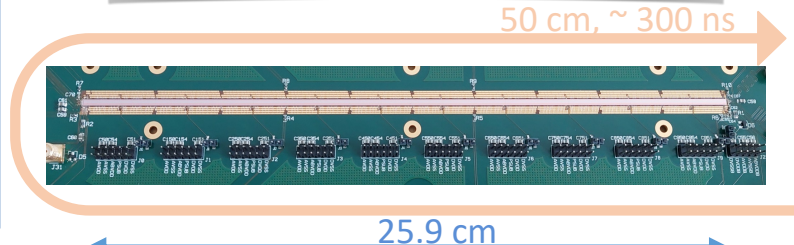
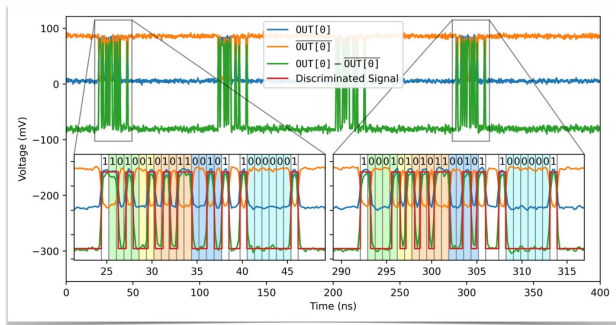


ER1: Dec 2022: Learning about stitching

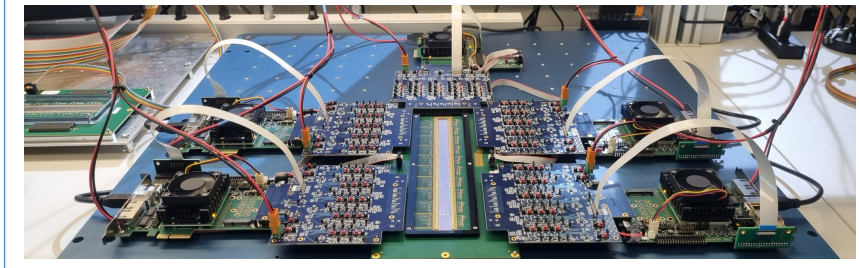
Two stitched sensors with 10 repeated units:
Both functional, learnings to be included in ER2

MOST (25.9 cm x 0.25 cm):

- 18 μm pitch, very densely designed pixel matrix
- Global power distribution + conservatively designed highly granular power switches to switch off faulty parts
- Asynchronous, hit-driven readout, low power consumption + timing information
- Pulsing signal and output signals at the end of the chip, round trip more than 50 cm, ~ 300 ns, with ~ 800 repeaters, all 256 signal lines functional



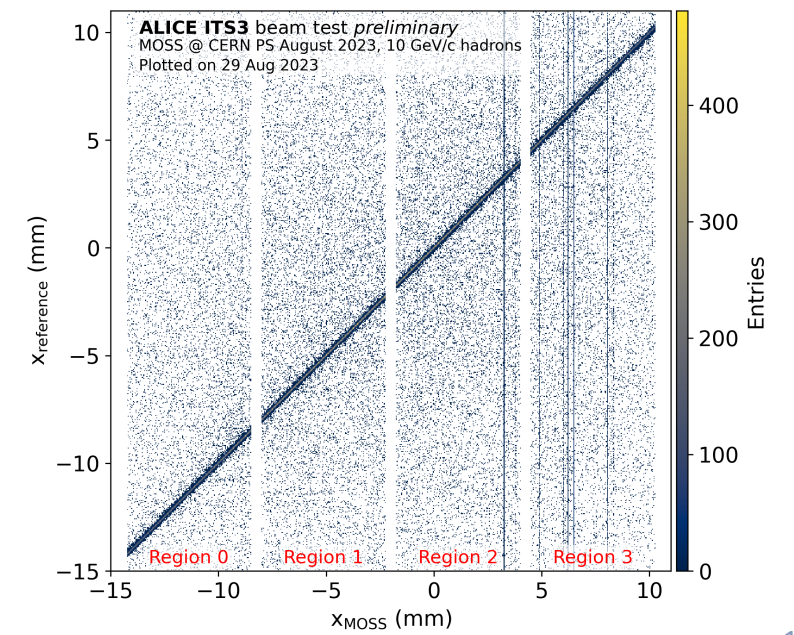
See presentation from L. Aglietta, posters from A. Villani and K. Gautam
Last EP R&D report: <https://cds.cern.ch/record/2891650>
ITS3 TDR: <https://cds.cern.ch/record/2890181?ln=en>



MOSS (25.9 cm x 1.4 cm):

- Top half 22.5 μm pitch, bottom half 18 μm pitch
- Each half powered completely independently with 4 conservatively designed submatrices \rightarrow many power domains
- Synchronous readout

Hit x-coordinate correlation between MOSS and reference ALPIDE telescope



CONCLUSIONS and OUTLOOK

- Key contributions of Marc Winter and Renato Turchetta helped us to move monolithic sensors for HEP to CMOS MAPS in mainstream CMOS technology with complex full CMOS in-pixel circuitry, and to design the ALICE ITS2 detector with 10 m² of ALPIDE chips presently taking data.
- 10 years of experience with 180 nm enabled fast qualification of the 65 nm technology for HEP and the exploration of wafer-scale sensors for ITS3, opening perspectives for other projects like ALICE3. Some foundry flexibility has allowed greatly improved sensor timing, radiation tolerance and operating margin based on general principles applicable to different technologies.
- The increasing complexity of Monolithic Active Pixel Sensors requires digital-on-top design techniques and verification by a team of expert chip designers, and sensor optimization and simulation by device/TCAD/Monte Carlo experts. Our community needs to preserve critical mass and know-how, and to concentrate resources exploiting convergence in sensor requirements for different future HEP applications.
- Large area pixel detectors are enabling devices for cutting edge research fields and practical applications in HEP, medical imaging, space-borne instruments, etc, illustrated by the interest in chips like ALPIDE, some of the examples mentioned by Renato and Marc, and other developments like Medipix/Timepix.

CONCLUSIONS and OUTLOOK

- **3D wafer stacking** now allows the connection of a readout wafer to a detector wafer, and deliver the fully finished diced assemblies to the customer. This **reduces the distinction with hybrid sensors**, but provides **opportunities well beyond** with multiple connections within each pixel and stacking of even more than two wafers.
- **Unprecedented integration** in electronics systems continues to be driven by the computation needs of AI. Stitching and wafer stacking brings pixel pitches around 10 um within reach. The **circuitry on a monolithic sensor** allows the **mitigation of local, otherwise fatal defects** for large, even wafer-scale sensors. Efficient volume test, assembly, and mounting, together with significant progress towards lower power densities and on-chip resistive drops, will be **enablers for large area detectors**, and this for practically all applications in HEP.
- CMOS monolithic sensors will become widely applied in HEP, in tracking, calorimetry and timing detectors. Non-negligible **MAPS production volumes** within HEP should allow our community to **impact not only the quality of its own measurements, but also society in general, with access to the most advanced technologies.**

THANK YOU !